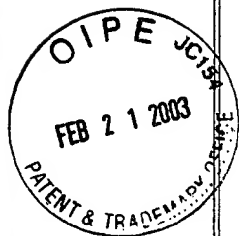


2823



PATENT
Customer No. 22,852
Attorney Docket No. 08244.0026

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Sun-oo KIM

Application No.: 09/739,743

Filed: December 20, 2000

For: METHOD FOR
MANUFACTURING INTERLAYER
DIELECTRIC LAYER IN A
SEMICONDUCTOR DEVICE

)
)
) Group Art Unit: 2823
)
) Examiner: W. Coleman
)
)
)
)
)
)

11 / AMST
B
3/3/03
✓8

TECHNOLOGY CENTER 2800

FEB 25 2003

RECEIVED

Assistant Commissioner for Patents
Washington, DC 20231

Sir:

AMENDMENT

In reply to the Office Action of November 21, 2002, please amend the application
as follows:

IN THE CLAIMS:

Please cancel claim 1 without prejudice or disclaimer of the subject matter
thereof, rewrite claim 2 in independent form, and amend claims 3-5, and 7, as follows:

2. (Amended) A method for manufacturing an interlayer dielectric layer, the
method comprising the steps of:

a) setting an active matrix provided with a substrate and interconnections formed
on the substrate in a chamber;

FINNEGAN
HENDERSON
FARABOW
GARRETT &
DUNNER LLP

1300 I Street, NW
Washington, DC 20005
202.408.4000
Fax 202.408.4400
www.finnegan.com